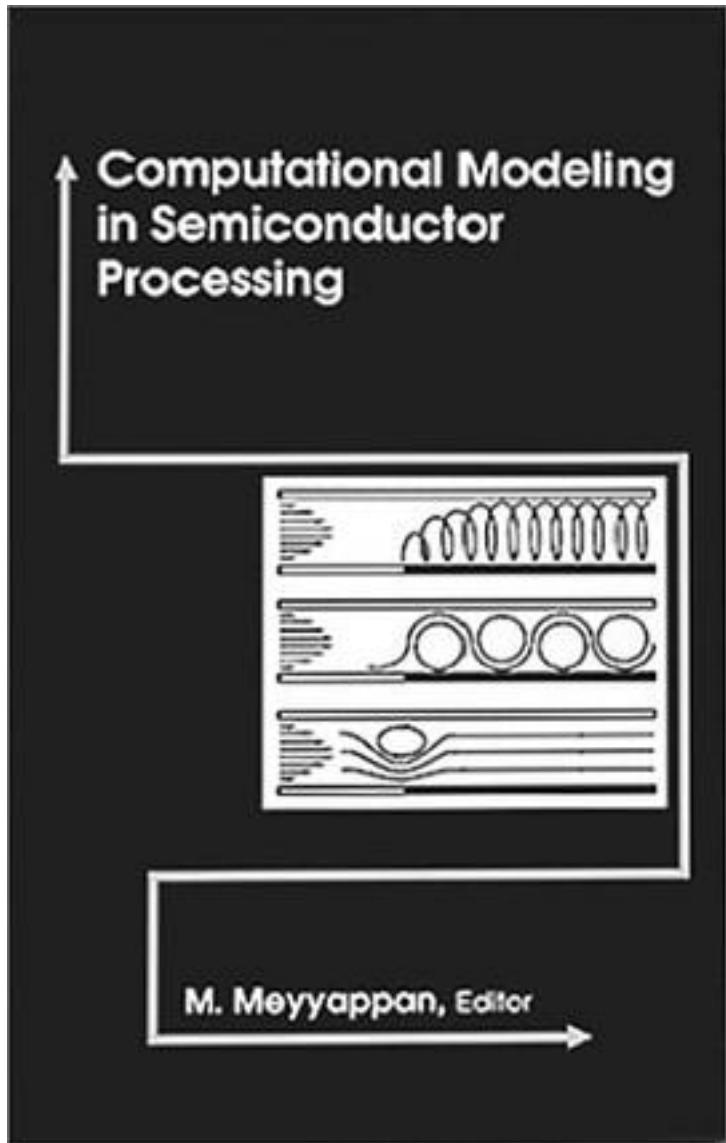# Computational Modeling in Semiconductor Processing

Computational Modeling in Semiconductor Processing_下载链接1_

著者:Meyyappan, M. 编

出版者:

出版时间:1995-1

装帧:

This text provides coverage of the models, governing equations and numerical techniques suitable for process simulation. It concentrates on such areas as chemical vapour deposition, metal-organic chemical vapour deposition, plasma processing, rapid thermal processing and crystal growth, as well as defining the basic principles of transport phenomena, gas phase and surface reactions in electronics materials processing. In addition, it explains how to apply practical numerical techniques used in process simulation, and presents the numerical methods necessary to produce simulation codes. The work is intended for those new to the field of process and equipment simulation in electronics materials processing, and also for the experienced modeller. It also contains coverage suitable for graduate students in materials science, and chemical, mechanical and electrical engineering.

作者介绍:

目录:

Computational Modeling in Semiconductor Processing_下载链接1_

标签

评论

Computational Modeling in Semiconductor Processing_下载链接1_

书评

[Computational Modeling in Semiconductor Processing_下载链接1_](#)